



wherein R_1 is a hydrogen atom or methyl, R_2 is an acid-labile tertiary alkyl group, and $m/(m+n)$ is 0.5 to 0.8, and

wherein R_2 is 2-methyl-2-norbornyl, 2-ethyl-2-norbornyl, 2-methyl-2-isobornyl, 2-ethyl-2-isobornyl, 8-methyl-8-tricyclo[5.2.1.0^{2,6}]decanyl, or 8-ethyl-8-tricyclo[5.2.1.0^{2,6}]decanyl.

5. A resist composition comprising:

(a) a photosensitive copolymer having a weight-average molecular weight of 3,000 to 100,000 and consisting essentially of first and second monomers represented by the following formulae:

